

In-Situ Spectroscopic Ellipsometry for Thermochromic CsPbI₃ Phase Evolution Portfolio

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Appendix

Tauc-Lorentz model

This model is from Jellison and Modine, APL 69,371-373 (1996). In this original paper, there is an error of calculation of the real part of the dielectric function.

In the Tauc-Lorentz model, the ϵ_2 is expressed as a product of the Tauc gap and the Lorentz model:

$$\epsilon = \epsilon_1 + i\epsilon_2$$

$$i\epsilon_2 = \begin{cases} \frac{1}{E} \cdot \frac{A \cdot E_0 \cdot C \cdot (E - E_g)^2}{2a} & (E > E_g) \\ 0 & (E \leq E_g) \end{cases}$$

$$\epsilon_1 = \frac{\pi}{2} \cdot P \cdot \int_{E_g}^{\infty} \frac{\xi \cdot \epsilon_2(\xi)}{\xi^2 - E^2}$$

where A is the amplitude parameter, C is the broadening parameter, and E_0 represents the peak transition energy. The corresponding ϵ_1 is obtained from ϵ_2 by the Kramers–Kronig relations.

Solving the integral:

$$\epsilon_1 = \frac{A \cdot C \cdot a_{\ln}}{2 \cdot \pi \cdot \xi^4 \cdot \alpha \cdot E_0} \cdot \ln \left[\frac{E_0^2 + E_g^2 + \alpha \cdot E_g}{E_0^2 + E_g^2 - \alpha \cdot E_g} \right] - \frac{A \cdot a_{a \cdot \tan}}{\pi \cdot \xi^4 \cdot E_0}$$

$$\cdot \left[\pi - a \cdot \tan \left(\frac{2 \cdot E_g + \alpha}{C} \right) + a \cdot \tan \left(\frac{\alpha - 2 \cdot E_g}{C} \right) \right] + \frac{2 \cdot A \cdot E_0}{\pi \cdot \xi^4 \cdot \alpha} \left\{ E_g \cdot (E^2 - \gamma^2) \cdot \left[\pi + 2 \cdot a \right. \right.$$

$$\cdot \left. \tan \left(\frac{\gamma^2 - E_g^2}{\alpha \cdot C} \right) \right] \right\} - \frac{A \cdot E_0 \cdot C \cdot (E^2 + E_g^2)}{\pi \cdot \xi^4 \cdot E}$$

$$\cdot \ln \left(\frac{|E - E_g|}{E + E_g} \right) + \frac{2 \cdot A \cdot E_0 \cdot C \cdot E_g}{\pi \cdot \xi^4} \cdot \ln \left[\frac{|E - E_g| \cdot (E + E_g)}{\sqrt{(E_0^2 - E_g^2)^2 + E_g^2 \cdot C^2}} \right]$$

where:

$$a_{\ln} = (E_g^2 - E_0^2)E^2 + E_g^2C^2 - E_0^2(E_0^2 + 3E_g^2)$$

$$a_{a \cdot \tan} = (E^2 - E_0^2)(E_0^2 + E_g^2) + E_g^2C^2$$

$$\xi^4 = (E^2 - \gamma^2)^2 + \frac{\alpha^2 \cdot C^2}{4}$$

$$\alpha = \sqrt{4 \cdot E_0^2 - C^2}$$

$$\gamma = \sqrt{4 \cdot E_0^2 - \frac{C^2}{2}}$$

In the actual calculation, the values of $|E - E_g|$ were chosen to not become zero. Therefore, the Tau-Lorentz model is determined by five parameters [ε_1 , A, C, E_g and E_0 .]

$$E(eV) = hv = \frac{1240}{\lambda(nm)}$$

$$\alpha(\lambda) = \frac{4\pi k(\lambda)}{\lambda}$$

The relationship between complex optical constant and complex dielectric constant:

$$\tilde{N} = n - ik$$

$$\varepsilon = \varepsilon_1 - i\varepsilon_2$$

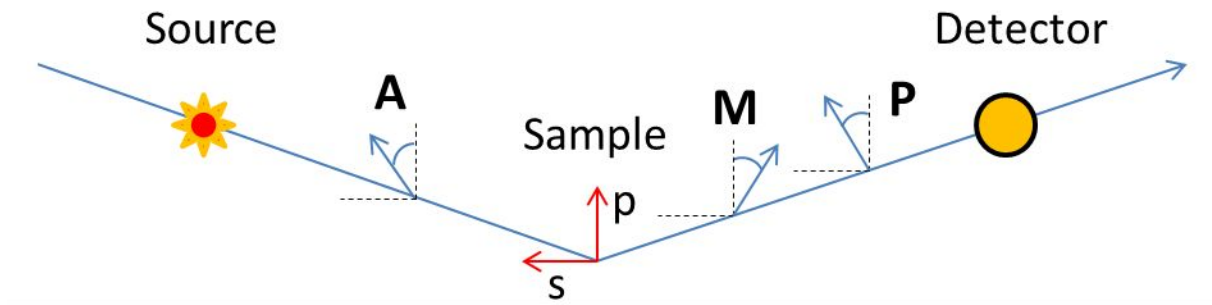
$$\varepsilon = \tilde{N}^2$$

$$n^2 - k^2 = \varepsilon_1$$

$$2nk = \varepsilon_2$$

Theoretical spectrum is adjusted to experimental one. Goodness of fit is given by value χ^2 . It should be as small as possible:

$$\chi^2 = \min \sum_{i=1}^n \left[\frac{(\Psi_{th} - \Psi_{exp})_i^2}{\Gamma_{\Psi,i}} + \frac{(\Delta_{th} - \Delta_{exp})_i^2}{\Gamma_{\Delta,i}} \right]$$



Detected electric field is deduced through Jones matrix product and incident electric field Jones vector:

$$\vec{E}_d = [AR_A SR_M MR_P - MP] \vec{E}_i$$

Only intensity is measurable, proportional to square of field.

$$I = \left| \overrightarrow{E_d} \right|^2 = I_O + I_S \sin \delta(t) + I_C \cos \delta(t)$$

In the general case for P, M, and A:

$$I_O = 1 - \cos 2\Psi \cos A + \cos 2(P - M) \cos 2M (\cos 2A - \cos 2\Psi) + \cos 2(P - M) \sin 2A \sin 2M \sin 2\Psi \cos \Delta$$

$$I_S = \sin 2(P - M) \sin 2A \sin 2\Psi \sin \Delta$$

$$I_C = \sin 2(P - M) [\sin 2M (\cos 2\Psi - \cos 2A) + \sin 2A \cos 2M \sin 2\Psi \cos \Delta]$$

By construction $P - M = 45^\circ$, then I_S I_C relation to Ψ and Δ becomes simple:

$$M = 0^\circ \pm 90^\circ \text{ and } A = \pm 45^\circ, \text{ then}$$

$$I_S = \pm_A \sin 2\Psi \sin \Delta \text{ and } I_C = \pm_M \pm_A \sin 2\Psi \cos \Delta$$

In this work, we use that Configuration II : $P - M = 45^\circ[90^\circ]$; $M=0^\circ[90^\circ]$; $A=45^\circ[90^\circ]$

$$I_S = \sin 2\Psi \sin \Delta \text{ and } I_C = \cos 2\Psi$$

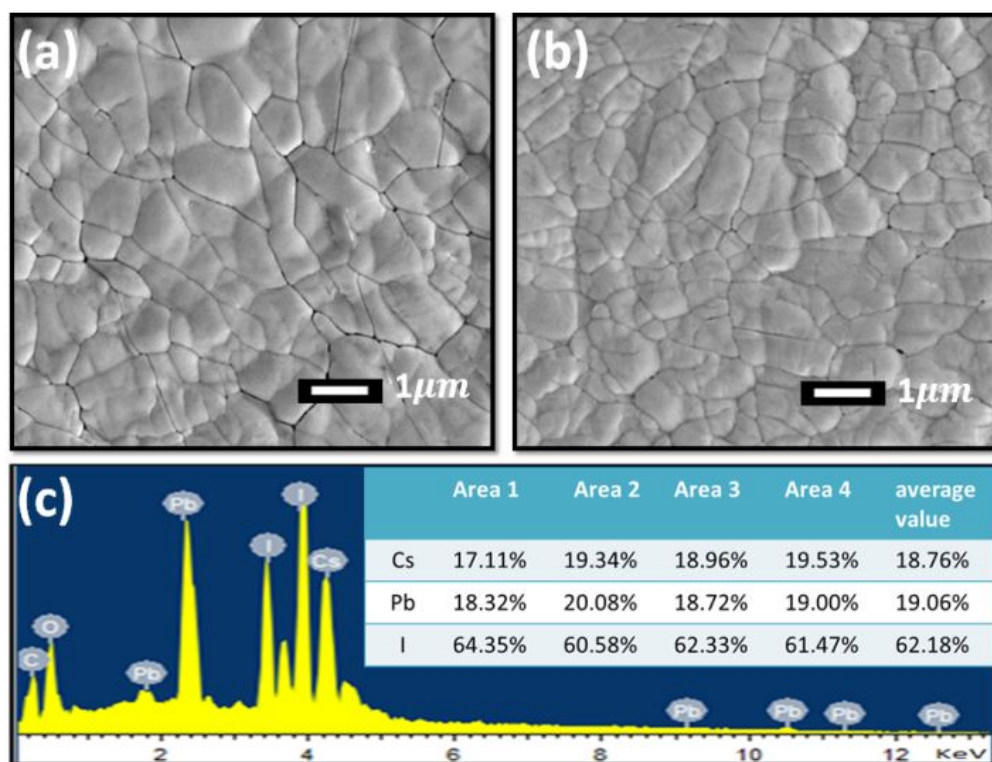


Figure S1 (a) SEM image of the δ -CsPbI₃ after once or twice (b) conversion between high and low temperature phase. (c) EDS of the δ -CsPbI₃ and the inset table is the percentage of element content in five different points.

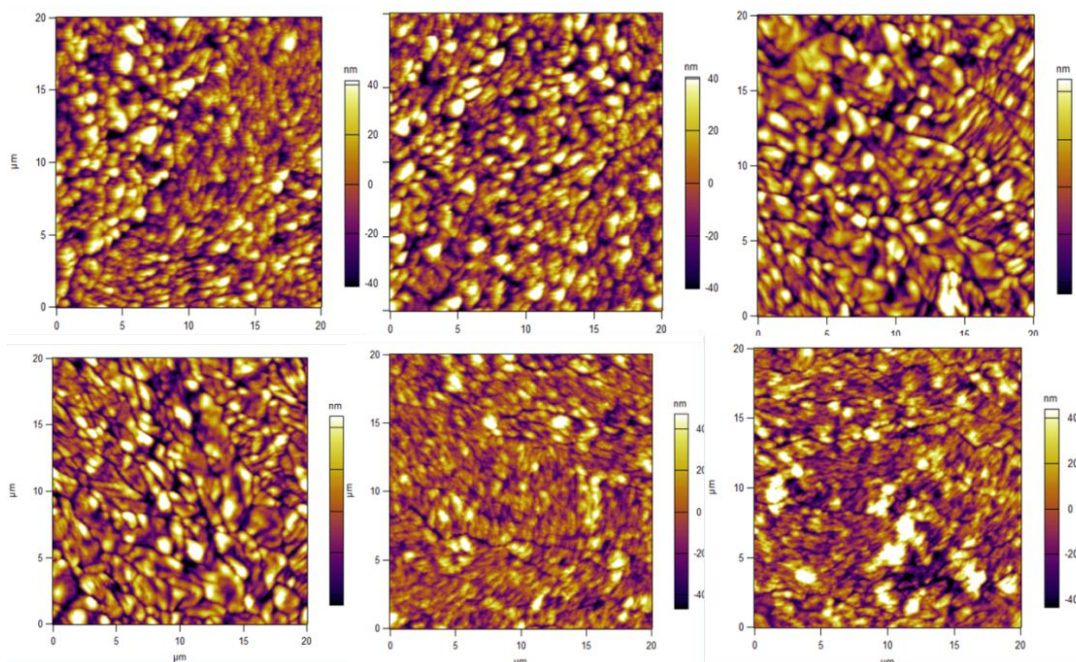


Figure S2 Atomic force micrographs of the δ -CsPbI₃ thin films.

Table S1 Roughness and average value of the above six δ -CsPbI₃ samples.

	RMS (nm)	Max (nm)	Min (nm)
Area1	19.085	85.149	-73.508
Area2	20.434	81.849	-70.881
Area3	22.965	123.020	-76.865
Area4	22.770	102.695	-83.505
Area5	17.238	88.743	-63.286
Area6	21.218	114.505	-72.673
average value	20.618	99.327	-73.453

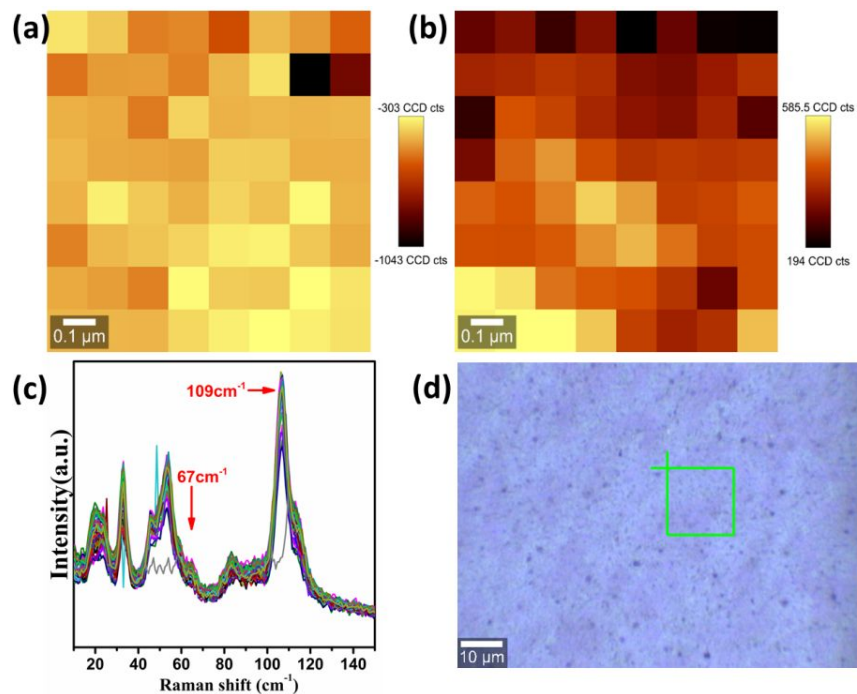
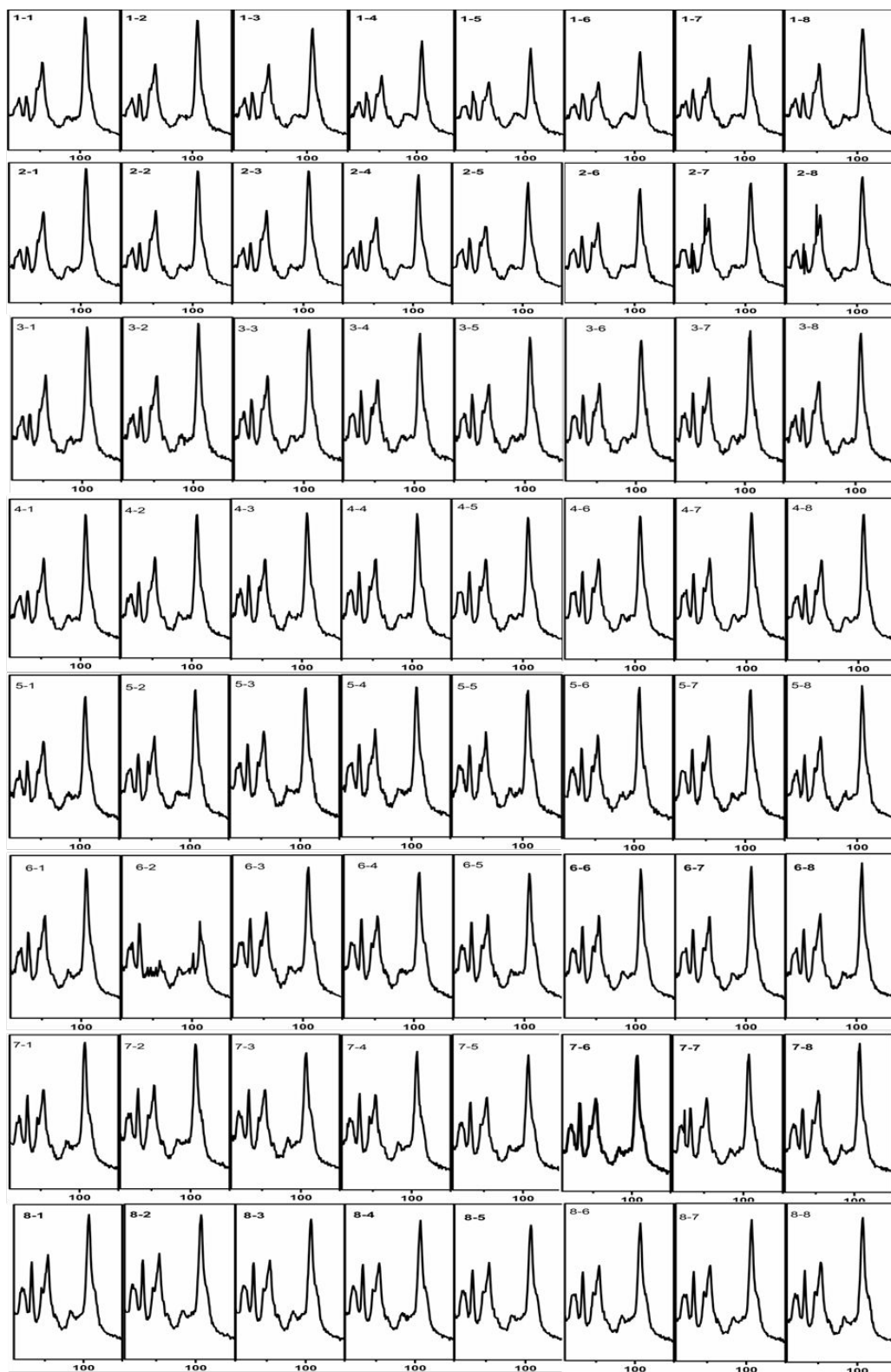


Figure S3 The α -CsPbI₃ thin films photography of in situ confocal low frequency Raman spectra at (a) 53 cm^{-1} and (b) 106 cm^{-1} . (c) is spectrums of in situ confocal Raman, and the characteristic peak position is marked by arrow. (d) is a microscopic photograph of the test point.

Intensity(a.u.)



Raman shift (cm⁻¹)

Figure S4 The in situ confocal Raman spectra of the δ -CsPbI₃ thin films at each point (resolution: 0.1*0.1 μm^2).

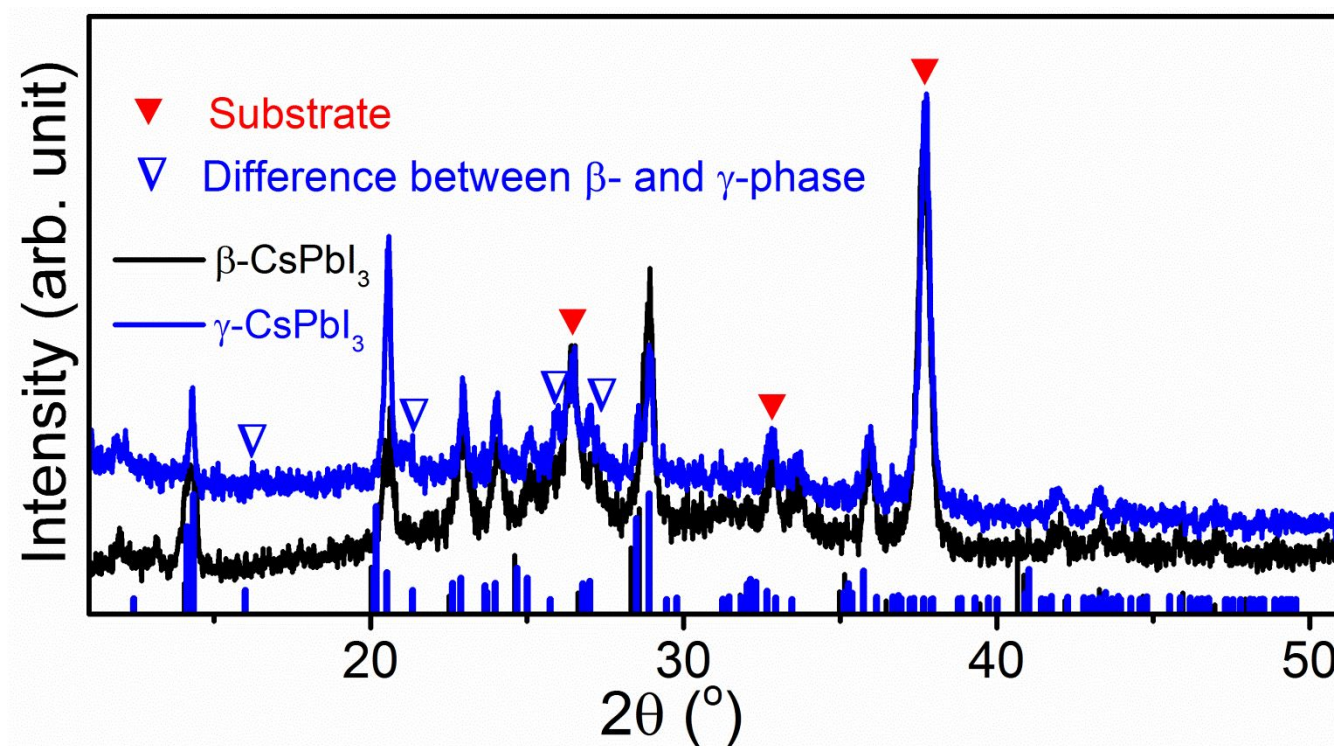


Figure S5 Comparison of the XRD difference of β - and γ -CsPbI₃ film.

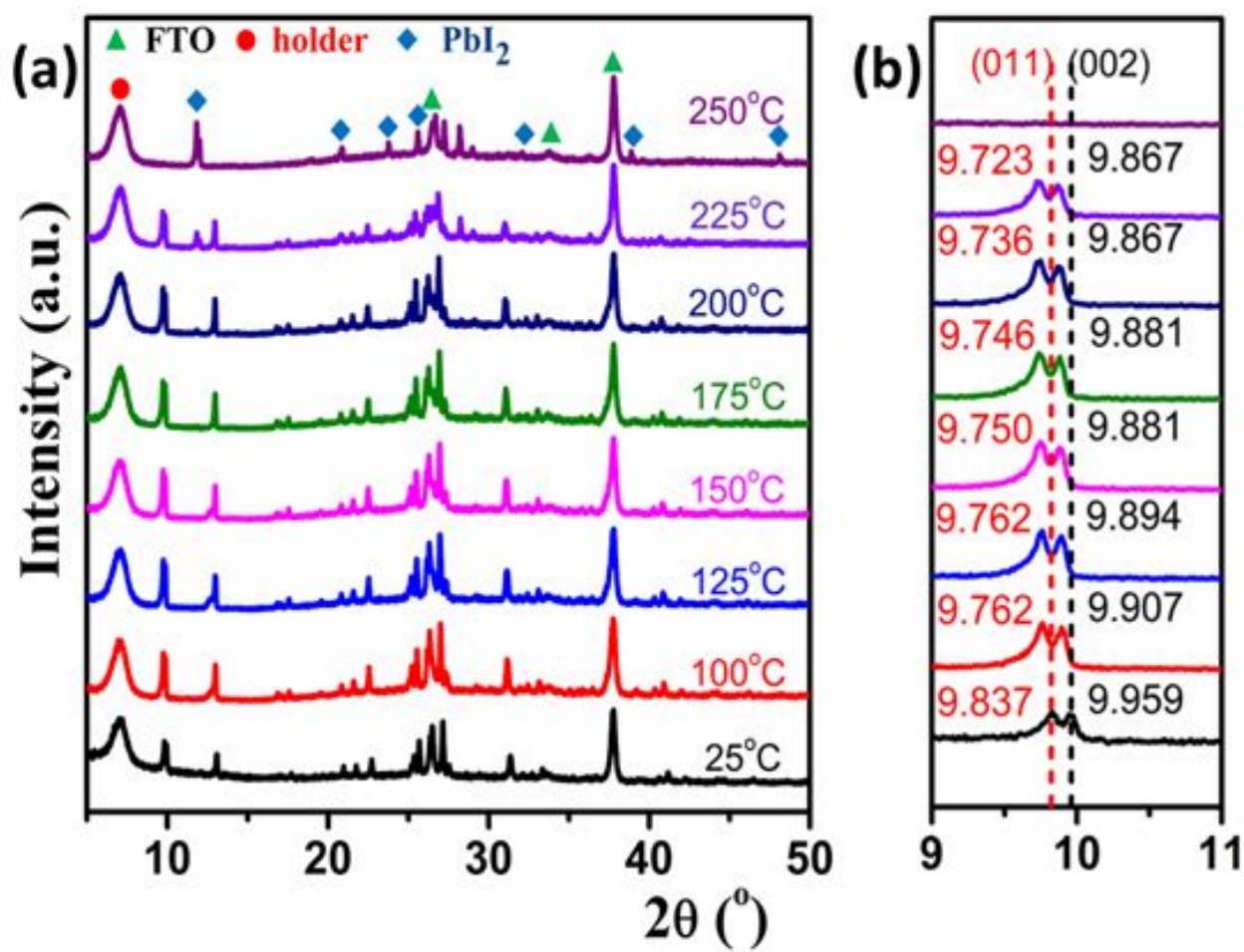


Figure S6 (a) Temperature dependent XRD of CsPbI₃ film measured in vacuum and enlarged view of the diffraction results in the 2-theta range of 9-11 °C.

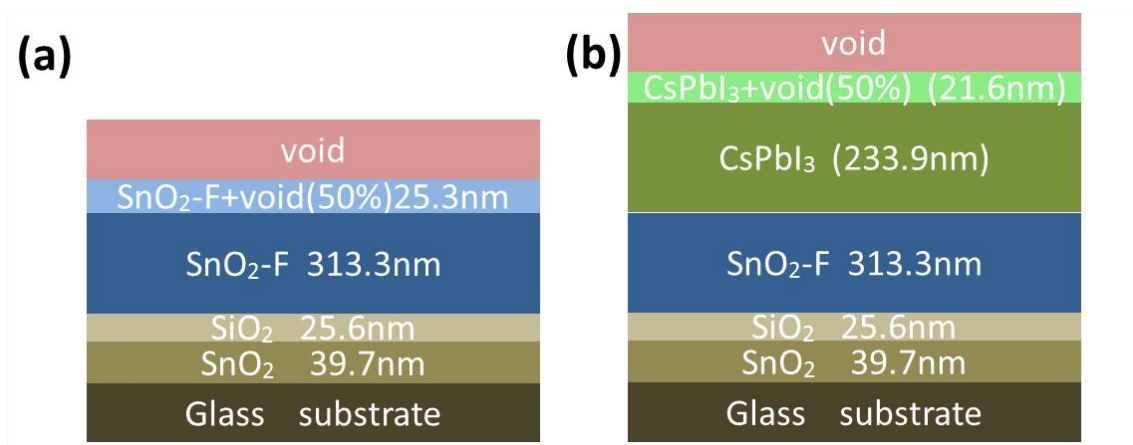


Figure S7 Schematics of the optical model of (a) the FTO substrate and (b) the CsPbI_3 thin films.

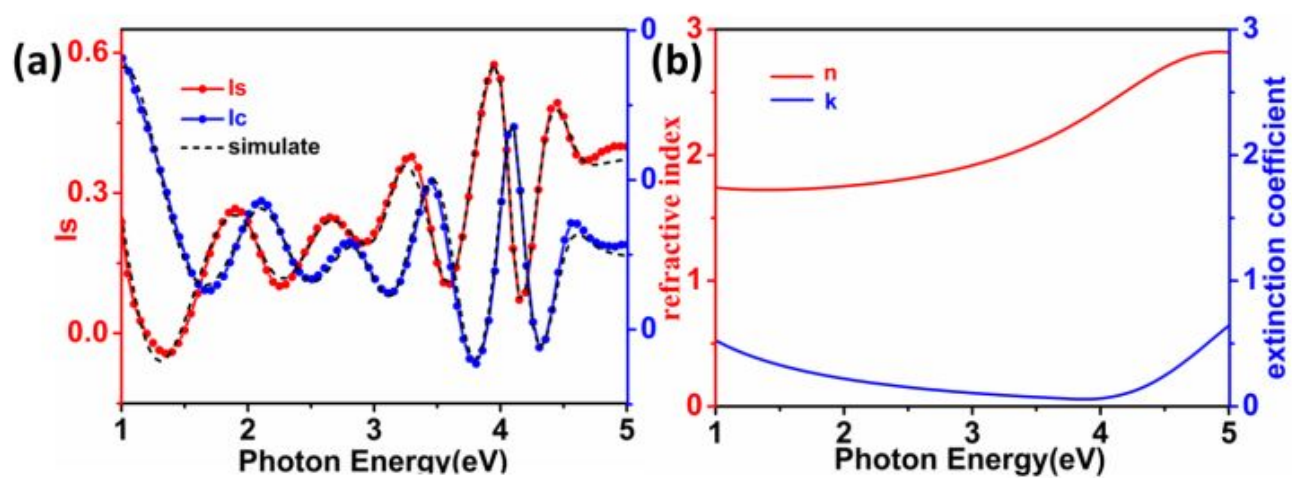


Figure S8 Measurement and analysis for the FTO substrate: (a) Ellipsometric experimental spectra (point lines) and simulate spectra (dotted lines) of the FTO substrate at a 70 ° angle of incidence. (b) Photo energy-dependent optical constants of the FTO layer.

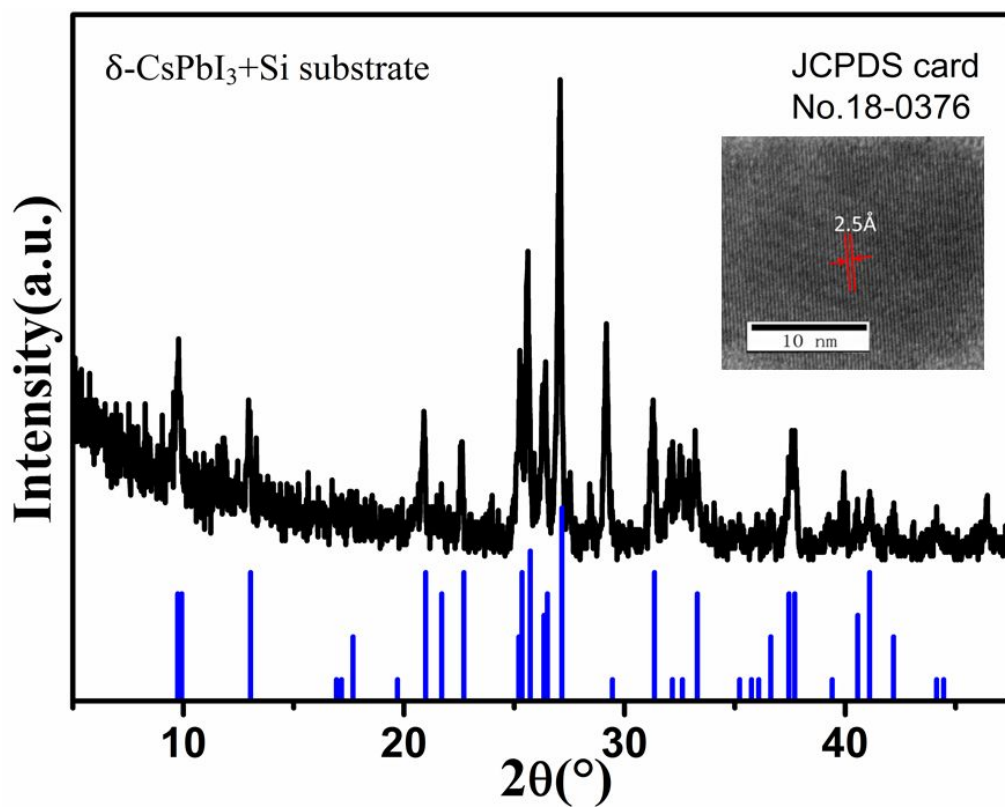


Figure S9 XRD patterns of the δ -CsPbI₃ thin film on silicon substrate. Inset shows a HRTEM image of δ -CsPbI₃ with a lattice fringe of 2.5 Å.

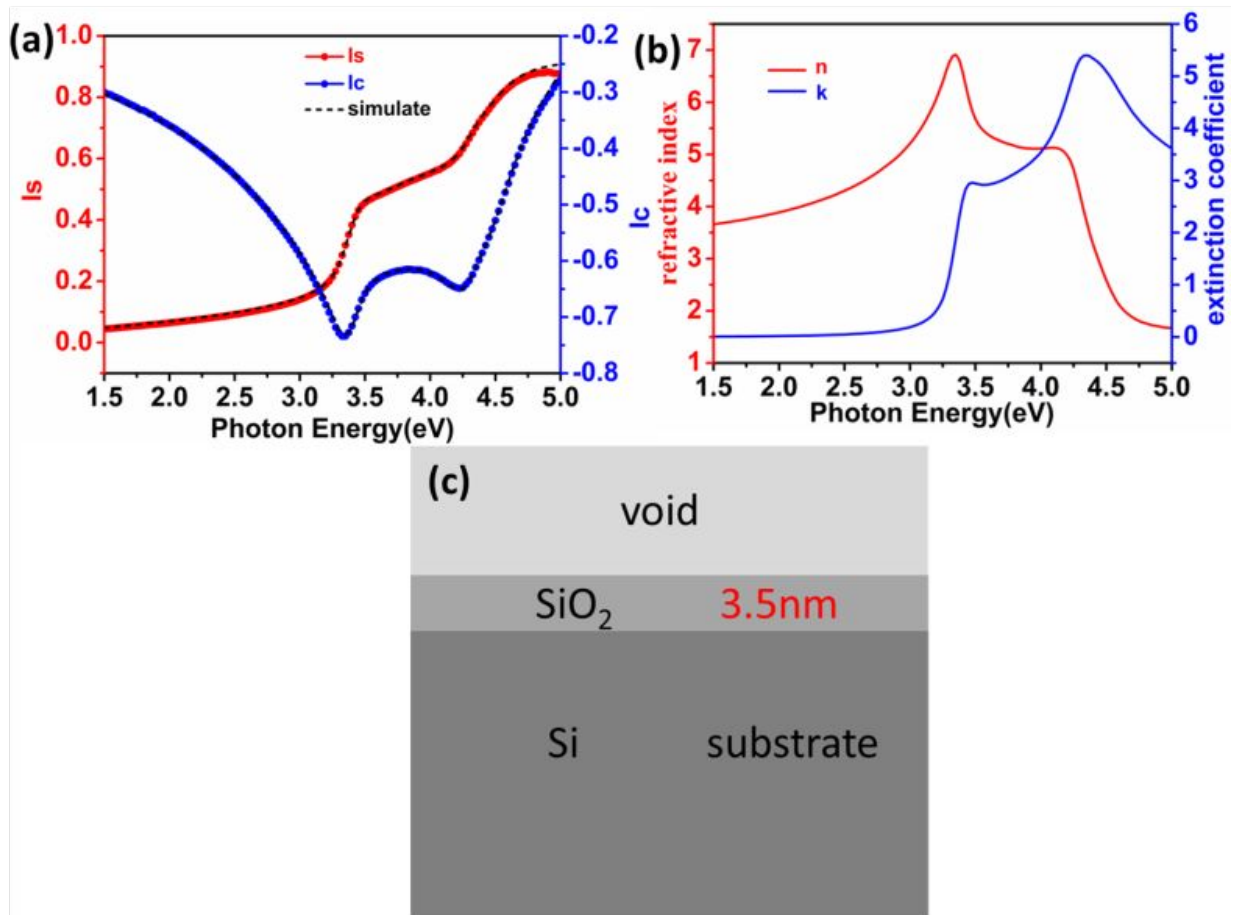


Figure S10 Measurement and analysis for the Si substrate: (a) Ellipsometric experimental spectra (point lines) and simulate spectra (dotted lines) of the Si substrate at a 70 ° angle of incidence. (b) Photon energy-dependent optical constants of the SiO₂ layer. (c) Schematic of the optical model. Results of the fitting parameters are marked in red in the model.

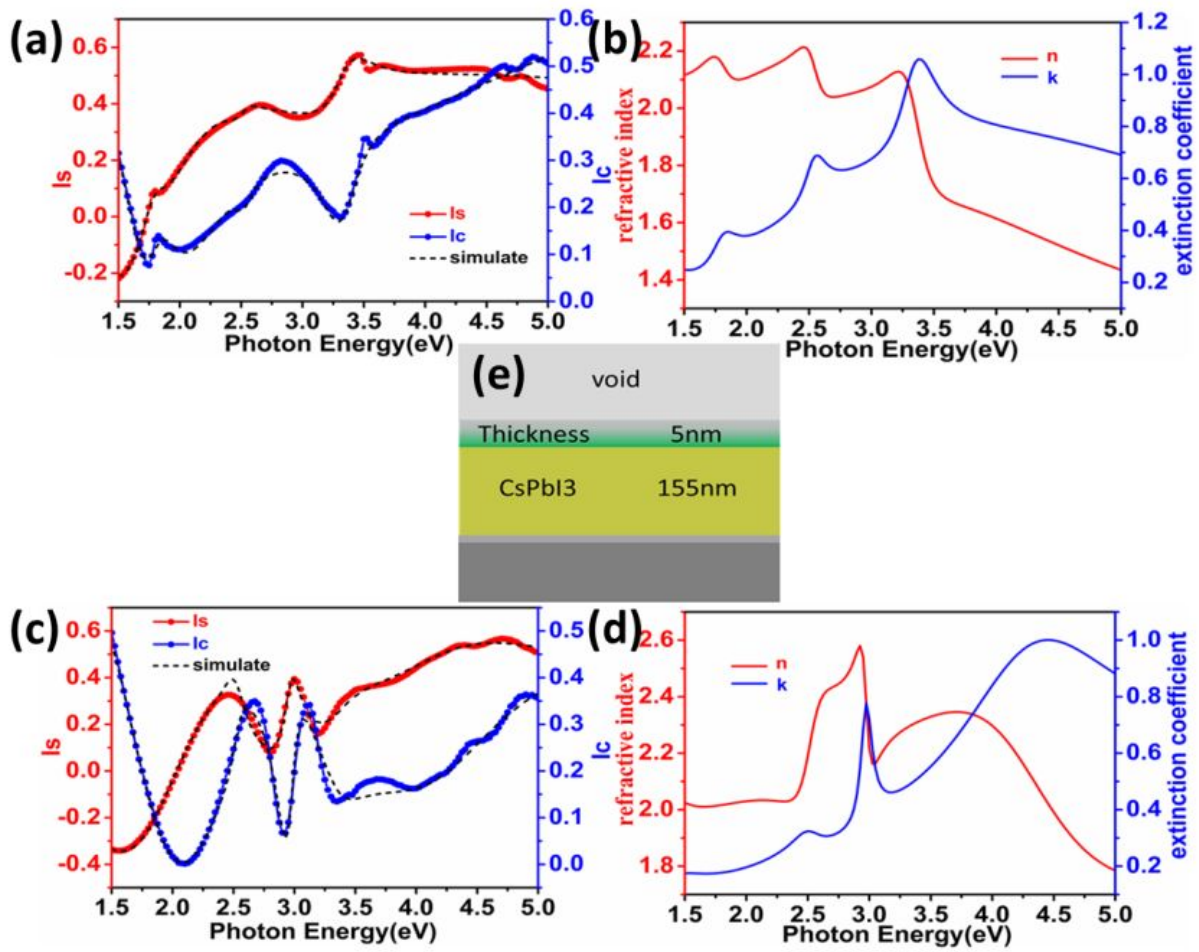


Figure S11 Measurement and analysis for the α -CsPbI₃ and the δ -CsPbI₃ thin film on the Si substrate: (a) and (c) Ellipsometric experimental spectra (point lines) and simulate spectra (dotted lines) of the α -CsPbI₃ and the δ -CsPbI₃ thin film at a 70 ° angle of incidence. (b) and (d) Photo Energy-dependent optical constants of the α -CsPbI₃ and the δ -CsPbI₃ thin film layer. (e) Schematic of the optical model.

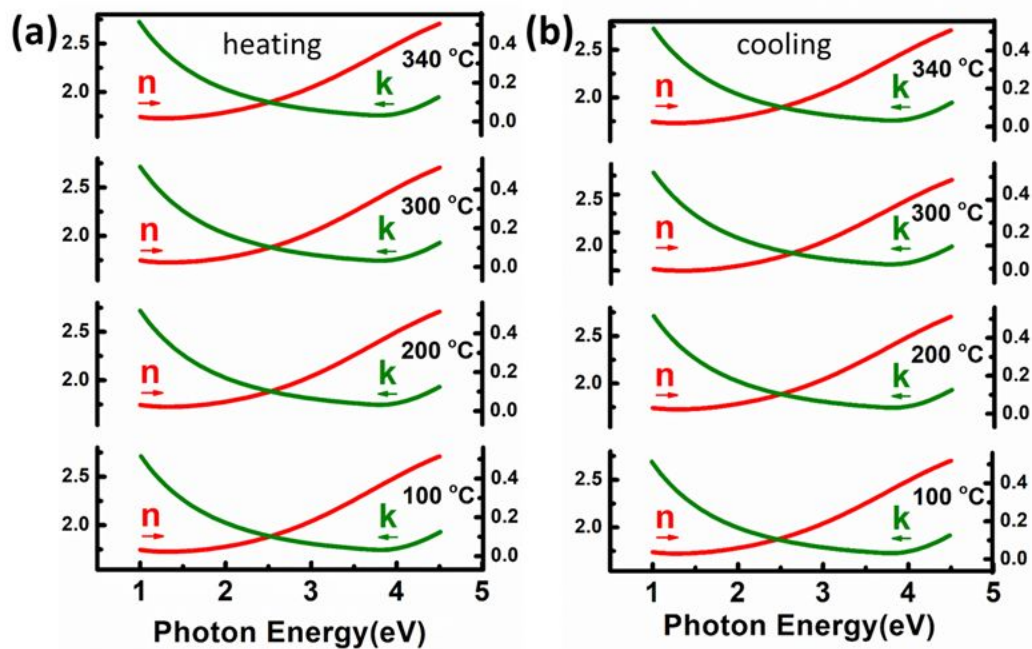


Figure S12 In-situ dynamic ellipsometry spectra of FTO substrate in (a) heating and (b) cooling processes from 100 to 360 °C.

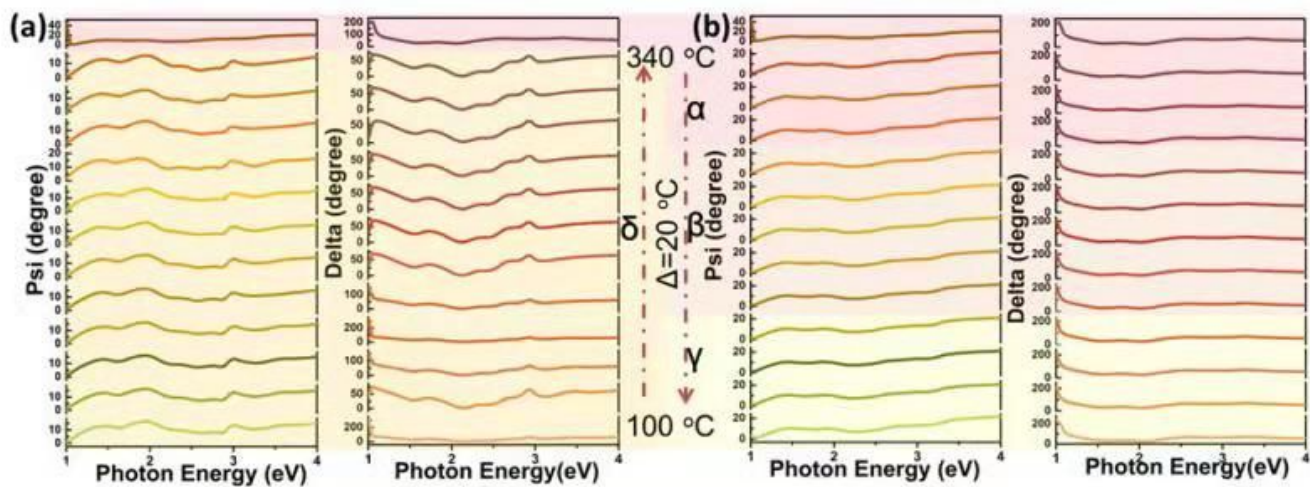


Figure S13 In-situ dynamic ellipsometry spectra of as-prepared CsPbI₃ film in (a) heating and (b) cooling processes from 100 to 360 °C.

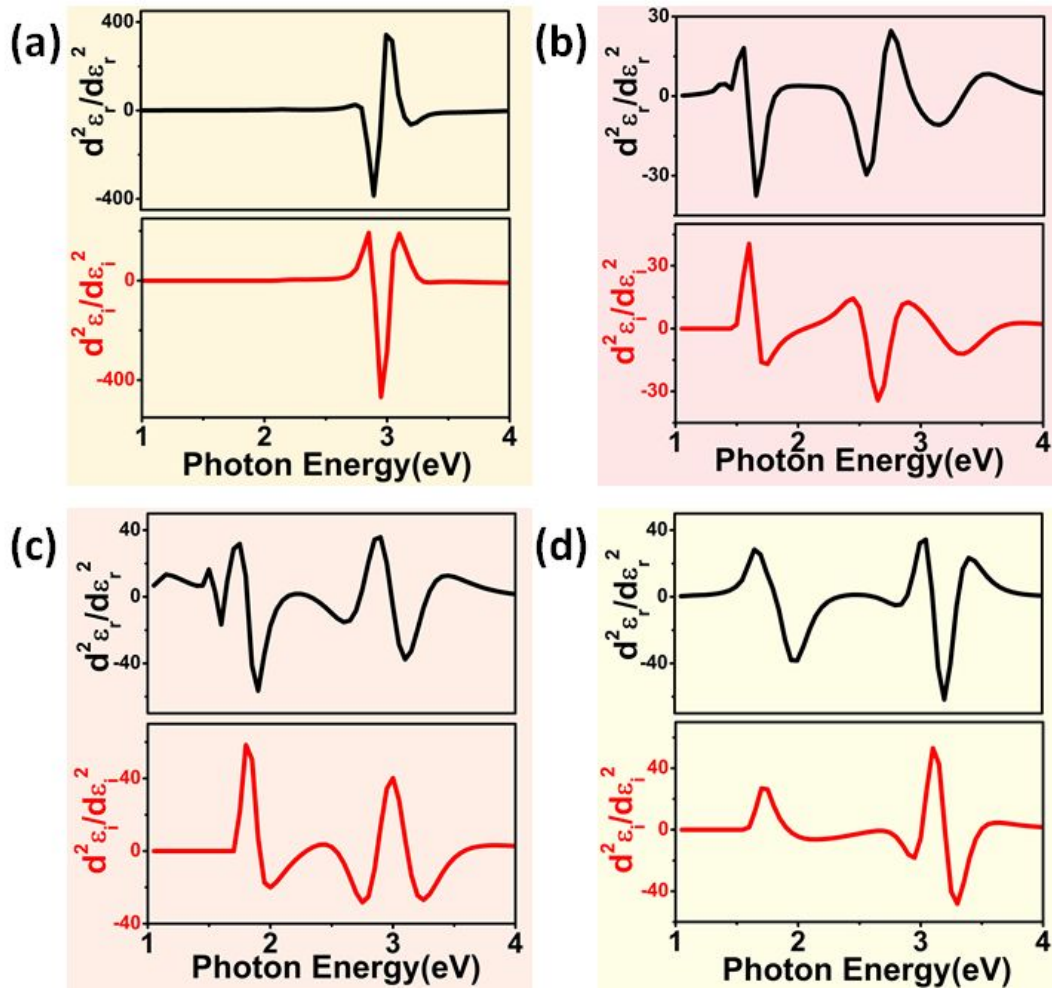


Figure S14 Second derivatives of the pseudodielectric function numerically calculated spectra for four phases of CsPbI₃ thin films: (a) δ (b) α , (c) β and (d) γ , respectively.